

Nanostructures induced by highly charged ions

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Ion beams in material science

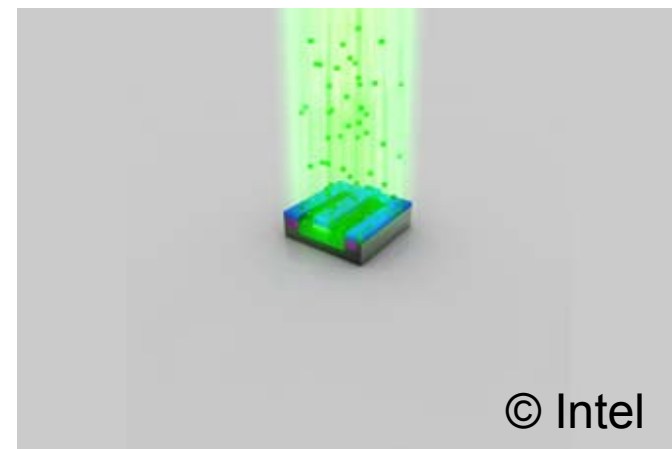
Ion beams have been traditionally used for:

Ion implantation: semiconductor industry

Surface modification: sputtering, sputter deposition
changing the surface properties

Material analysis: RBS, ERDA,
with sputtering: SIMS, SNMS,

...



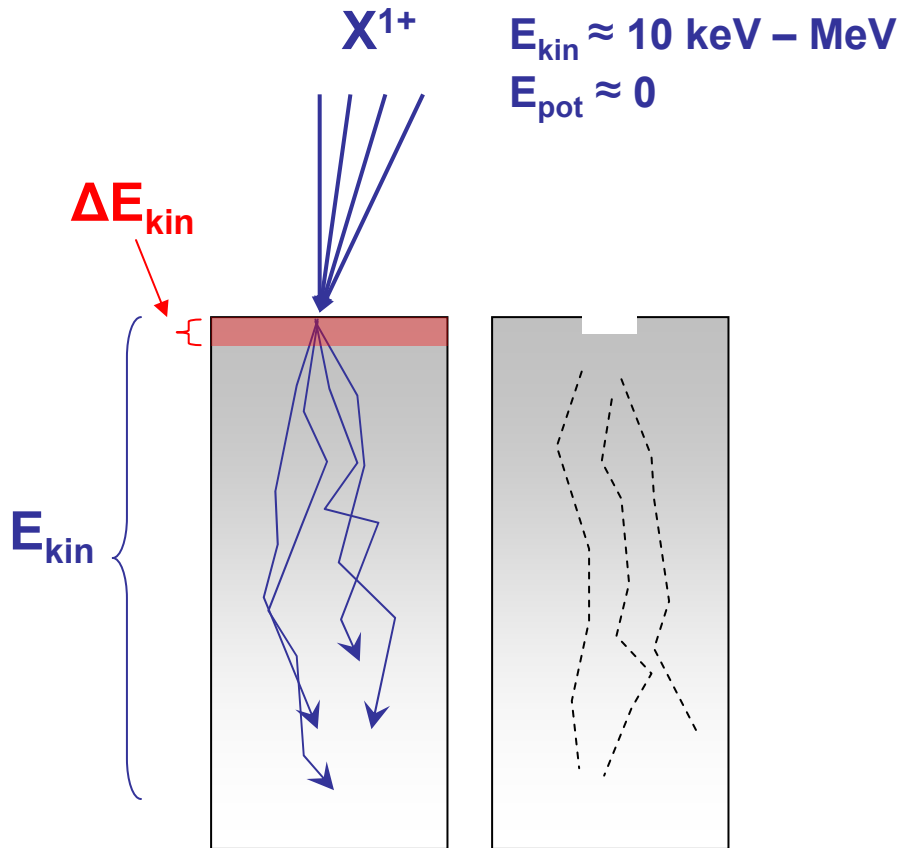
© Intel



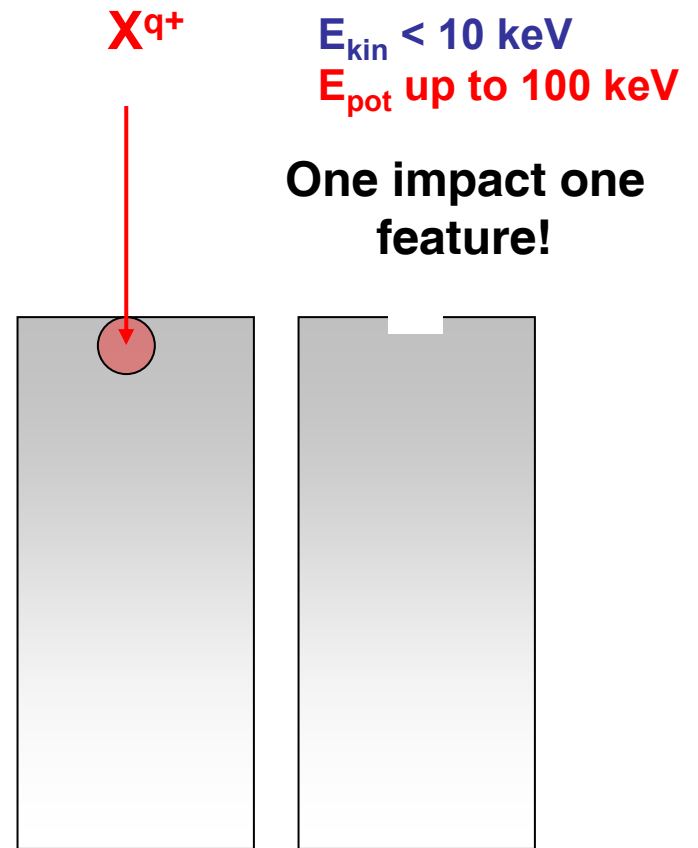
Where can highly charged ions be used with advantage?

New degree of freedom: potential energy

■ Conventional particle irradiation

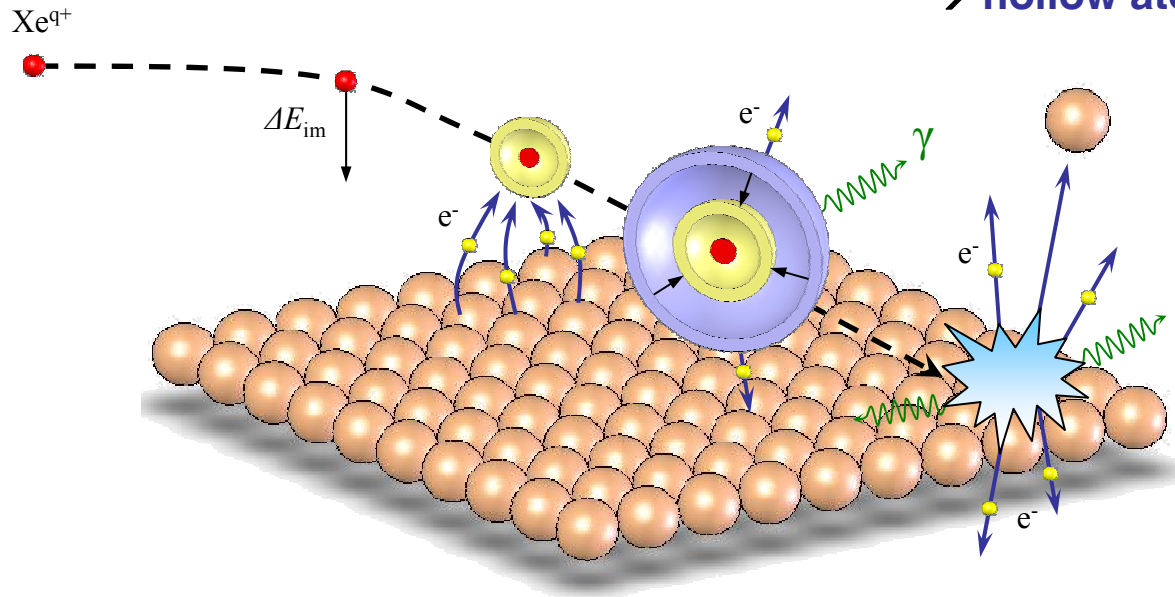


■ HCI irradiation



Localized electronic excitation similar to high power laser excitation!

- Interaction well understood in the frame work of the **Classical Over Barrier Model (COB)**



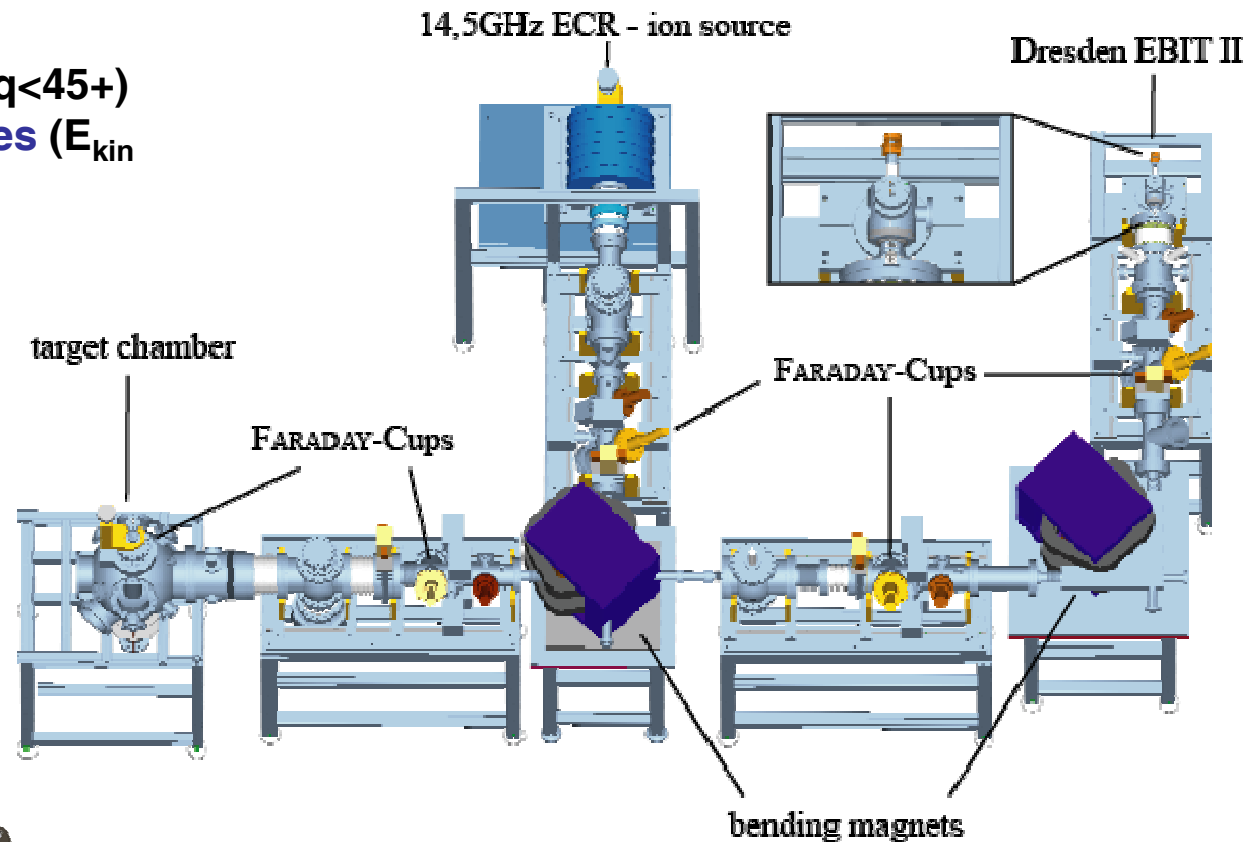
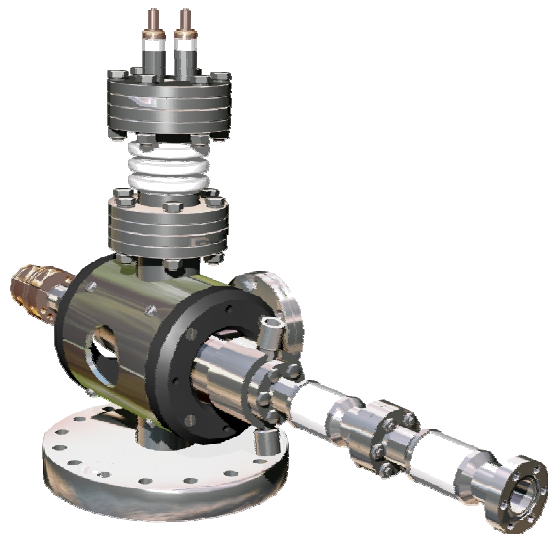
- Neutralization** involves **electron transfer** from the surface to the projectile into Rydberg orbitals
 → **hollow atom formation**

- Rapid relaxation** of the HA in front of the surface leads to emission of **numerous secondary electrons**

- Electrons** carry a major part of the ions initial potential energy into the surface and lead to permanent **structures on a nm scale**

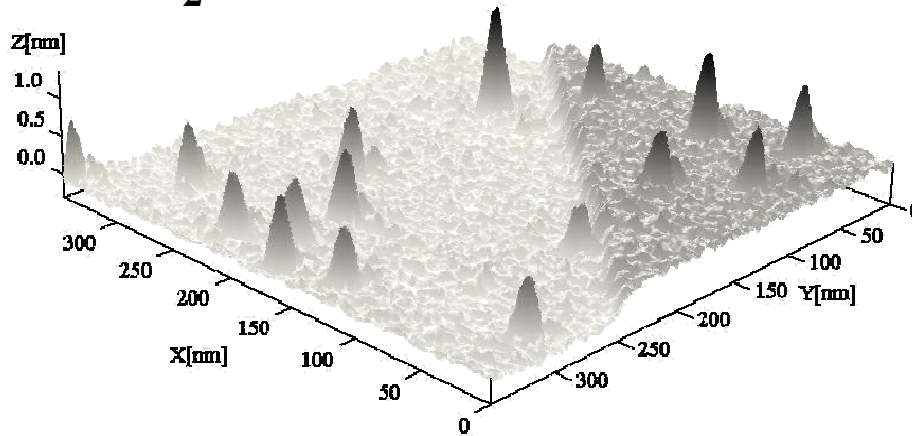
- Irradiation experiments at Rossendorf Two Source Facility

- Highest charge states ($q < 45+$) at lowest kinetic energies ($E_{\text{kin}} > 20 \text{ eV} \cdot q$)

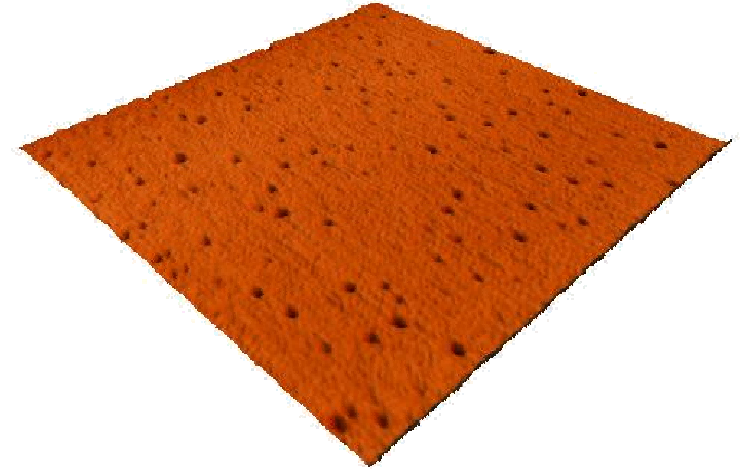


c-AFM characterization of the surface „ex-situ“

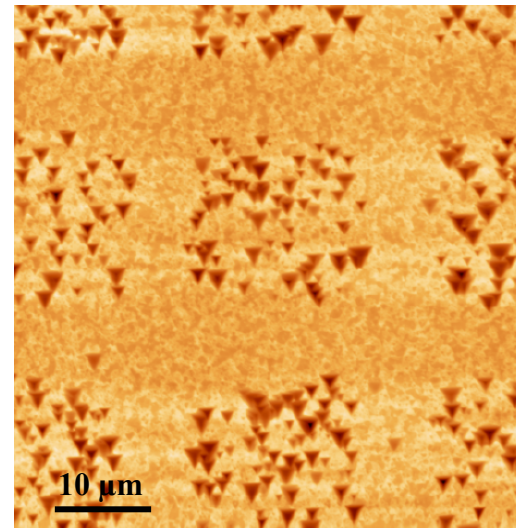
CaF₂



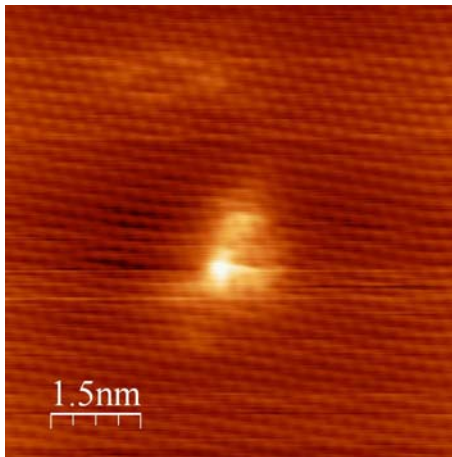
KBr



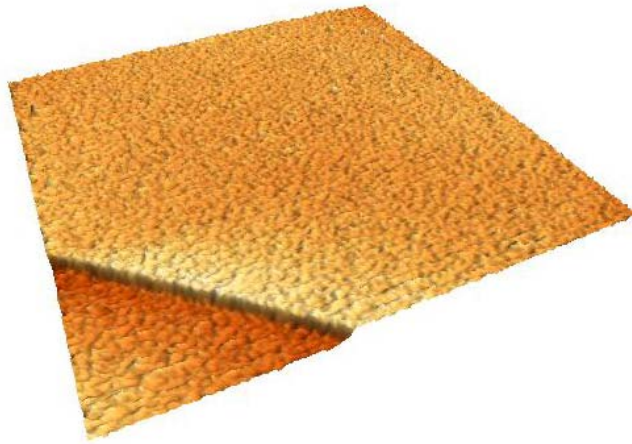
BaF₂



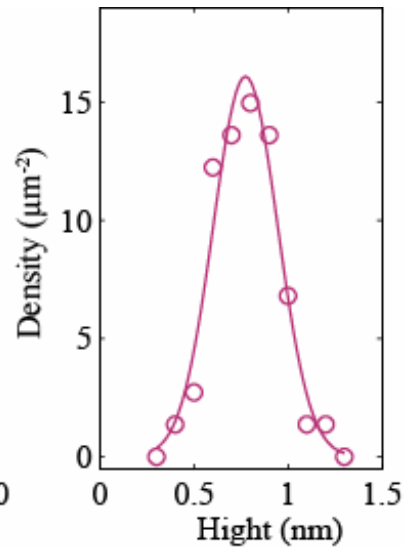
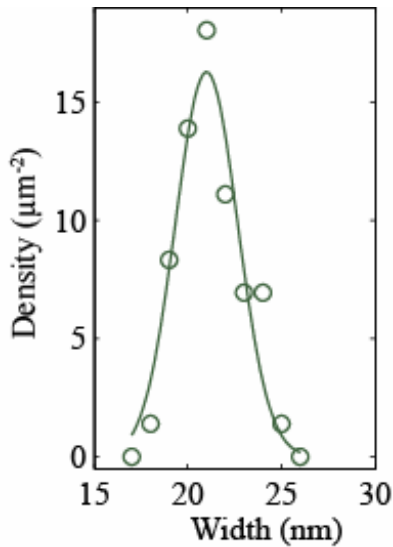
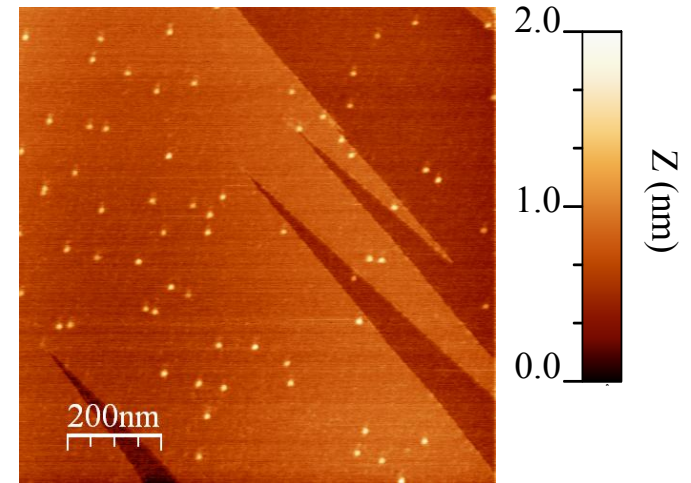
HOPG



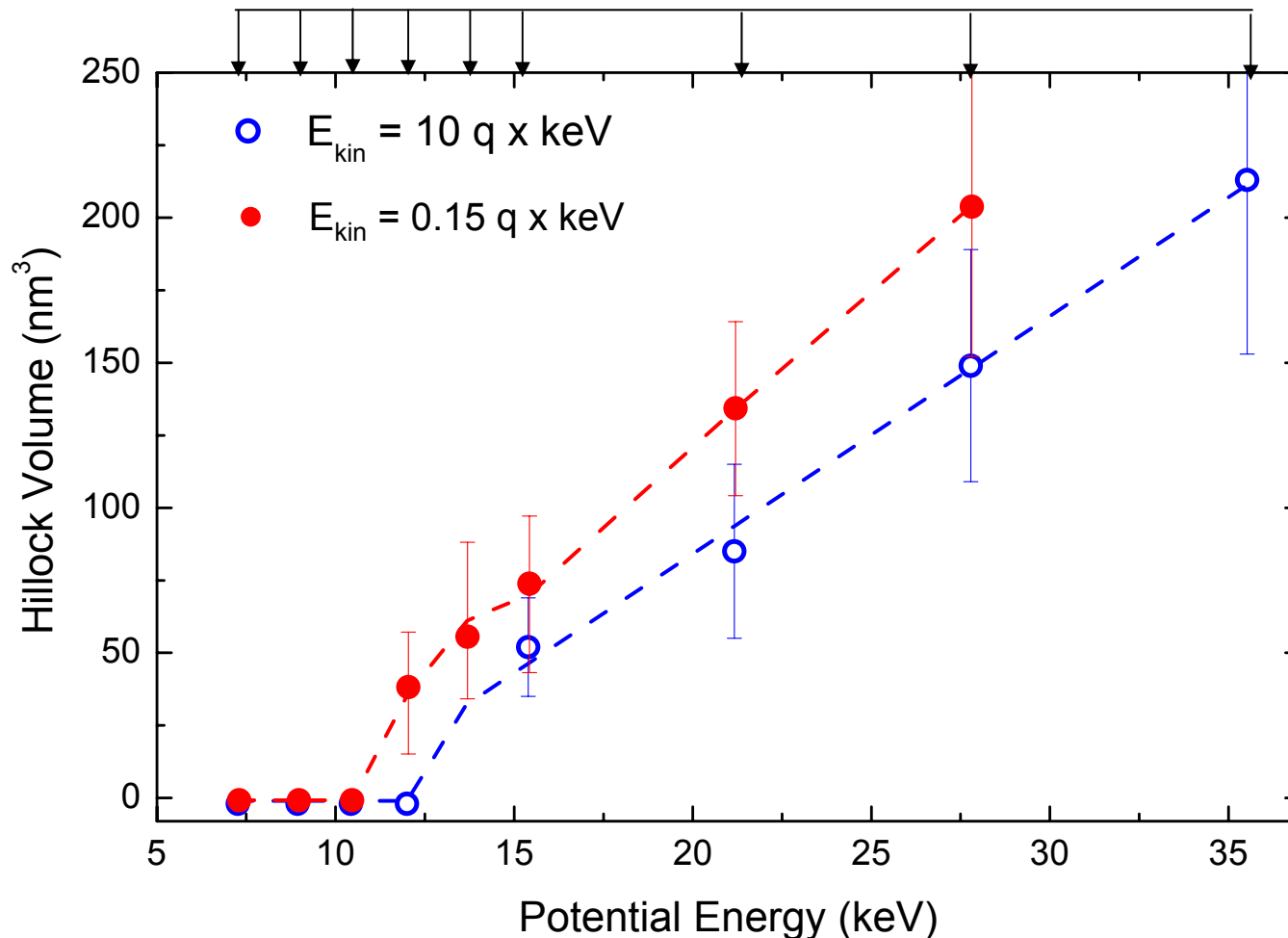
Hillocks on CaF_2 induced by highly charged ions



Xe^{33+} , $E_{\text{kin}} = 2 \text{ keV}\cdot\text{q}$



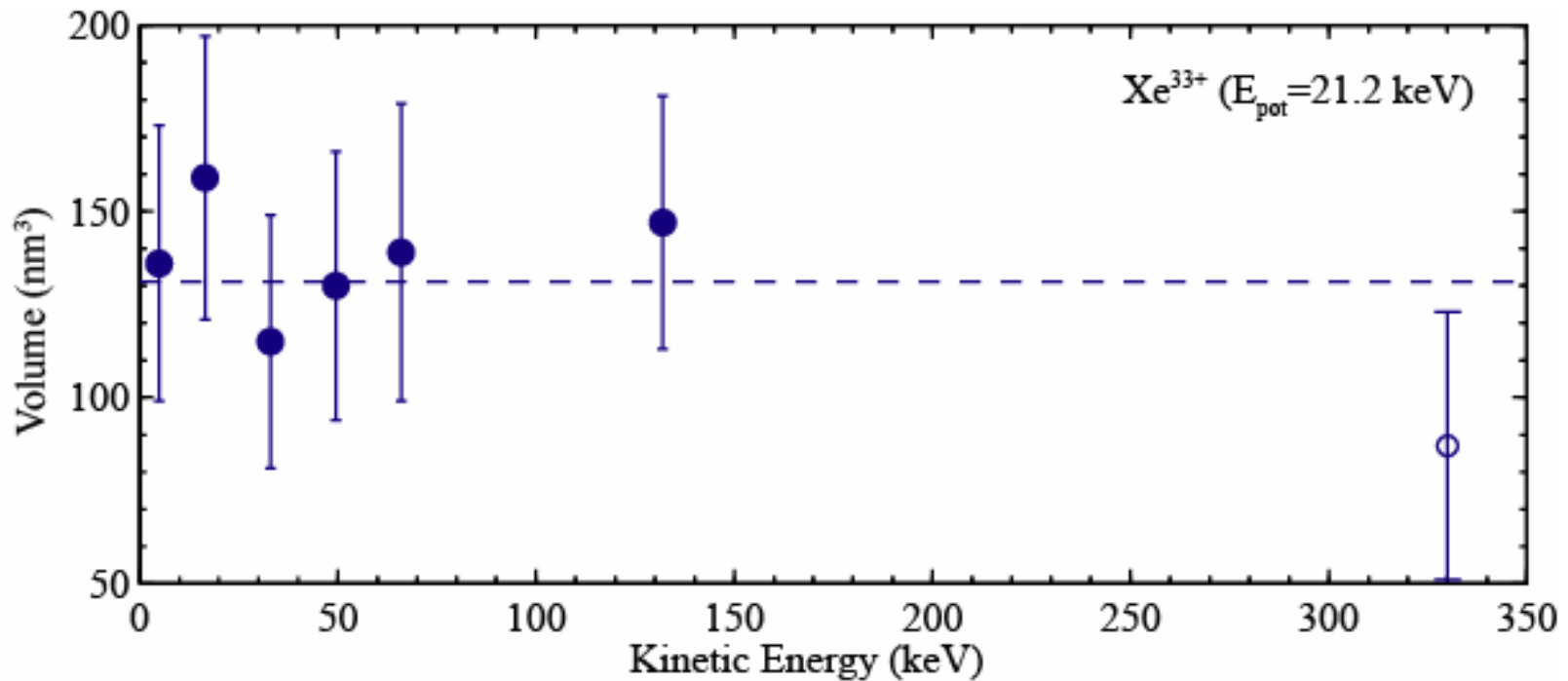
Xe^{q+} q = 24 26 27 28 29 30 33 36 40



Well defined **threshold** for hillock formation in **potential energy**

Linear increase of hillock volume with **pot. energy** upon **E_{crit.}**

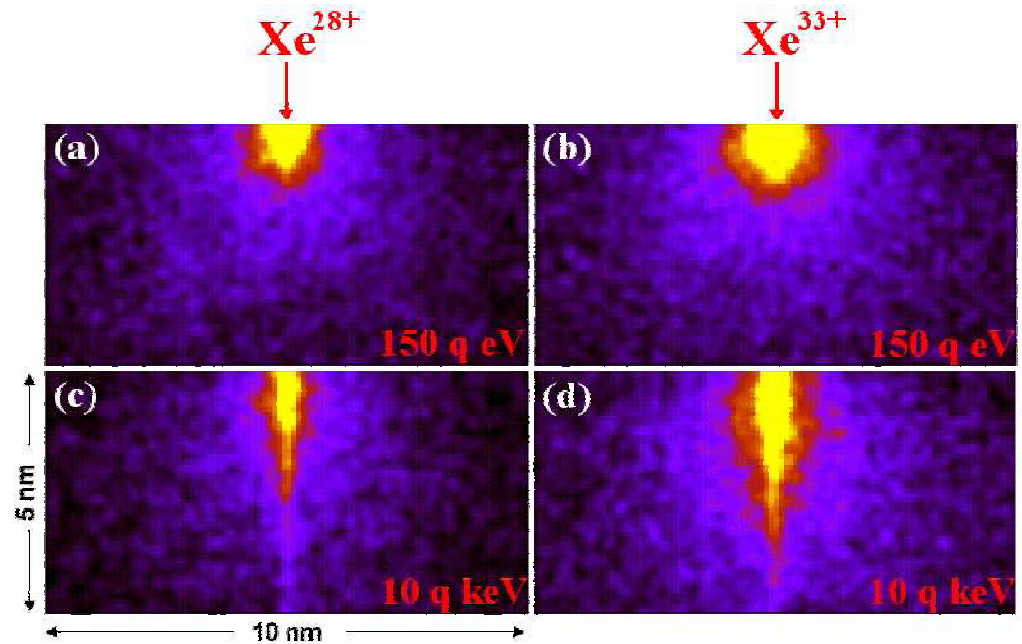
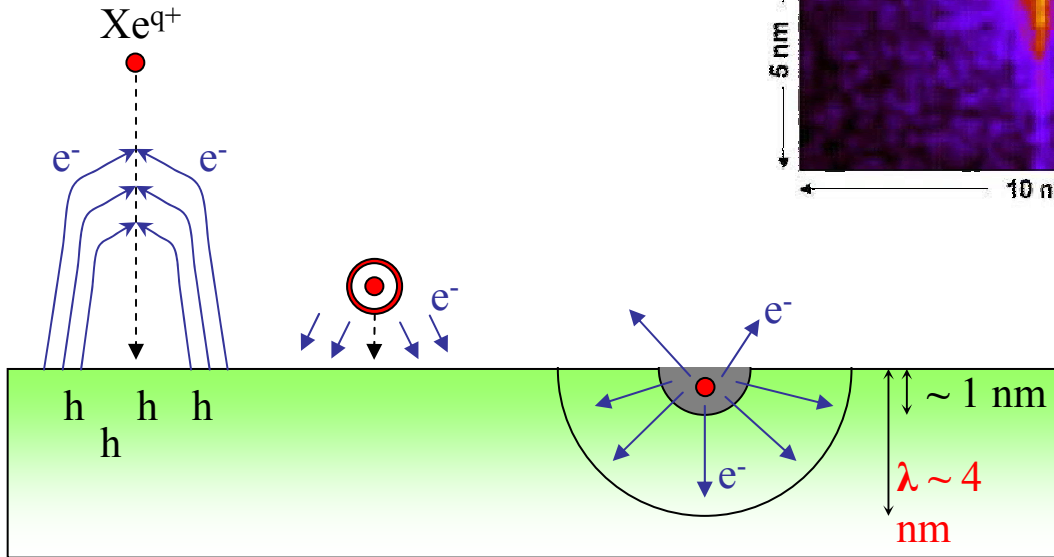
Slight shift of **E_{crit.}** with increasing **kinetic energy**



■ Hillock volume **independent** on kinetic energy over a wide range

■ For highest E_{kin} small shift towards **lower** hillock volume

- Electrons from HCl neutralization spread a major part of E_{pot} into a small region close to the surface
- Potential energy threshold related to melting energy
→ Local phase transition

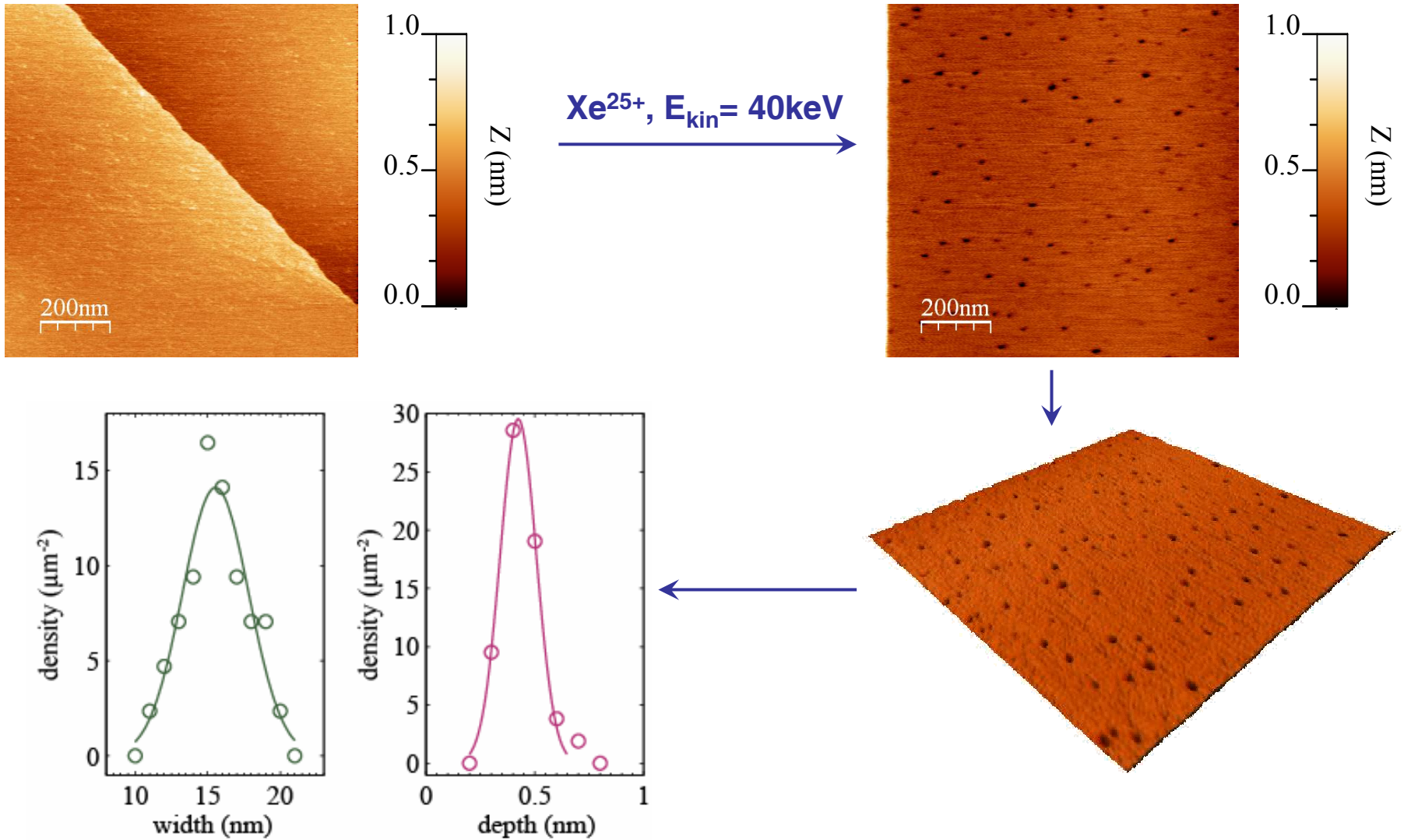


Detailed electron energy transport calculation

Inelastic thermal spike model (M. Toulemonde)

A. S. El-Said, R. Heller et al., PRL 100, 237601 (2008)

Pits on KBr induced by highly charged ions



potential energy



Xe^{5+} ($E_{\text{pot}} = 0.16 \text{ keV}$)

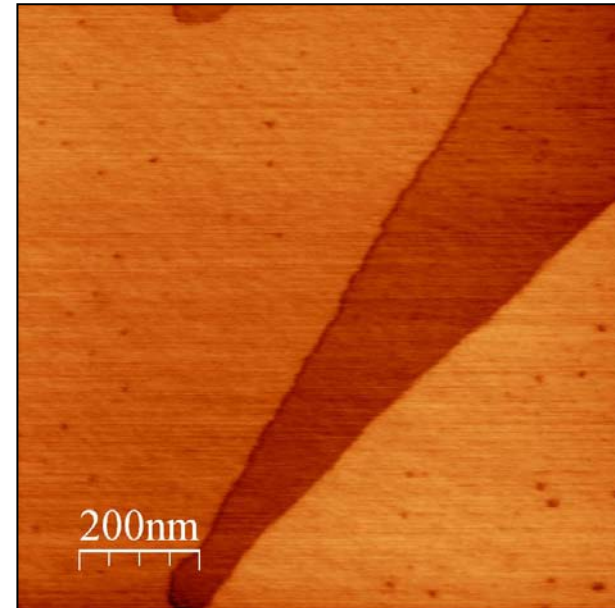
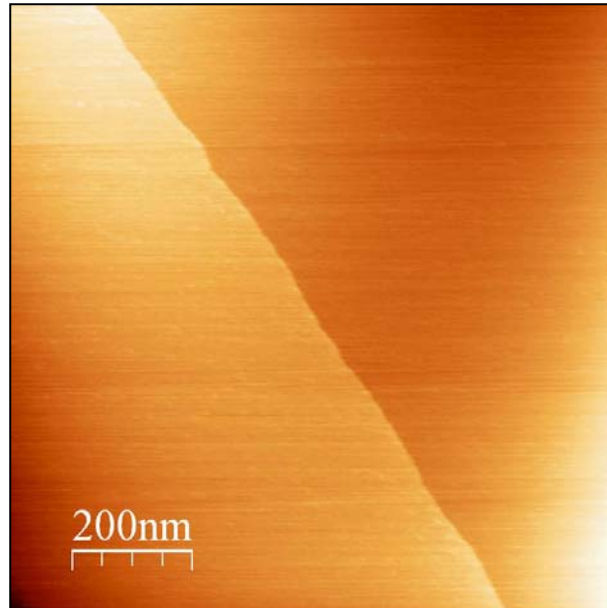
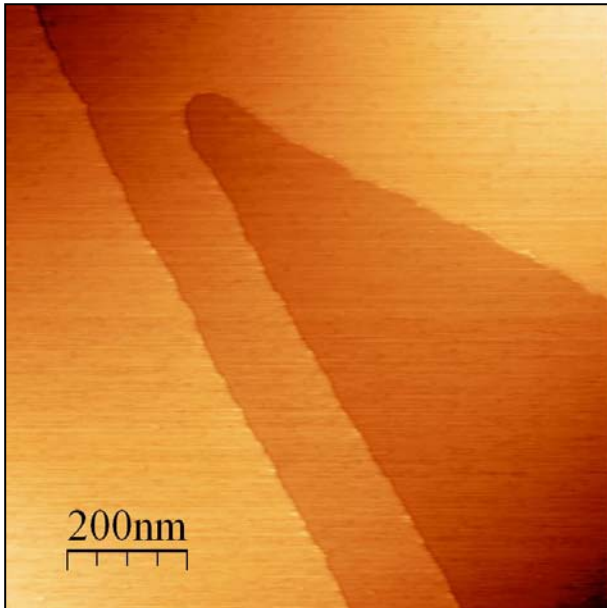
$E_{\text{kin}} = 4.0 \text{ keV}$

Xe^{10+} ($E_{\text{pot}} = 0.80 \text{ keV}$)

$E_{\text{kin}} = 4.0 \text{ keV}$

Xe^{34+} ($E_{\text{pot}} = 23 \text{ keV}$)

$E_{\text{kin}} = 4.0 \text{ keV}$



fluence $< 1 \cdot 10^{10} \text{ cm}^{-2}$

→ single ion impact

kinetic energy



Xe^{34+} ($E_{\text{pot}} = 23 \text{ keV}$)

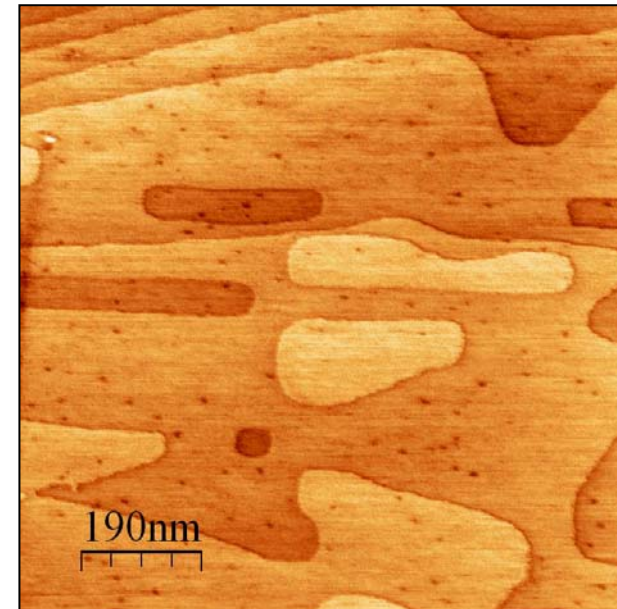
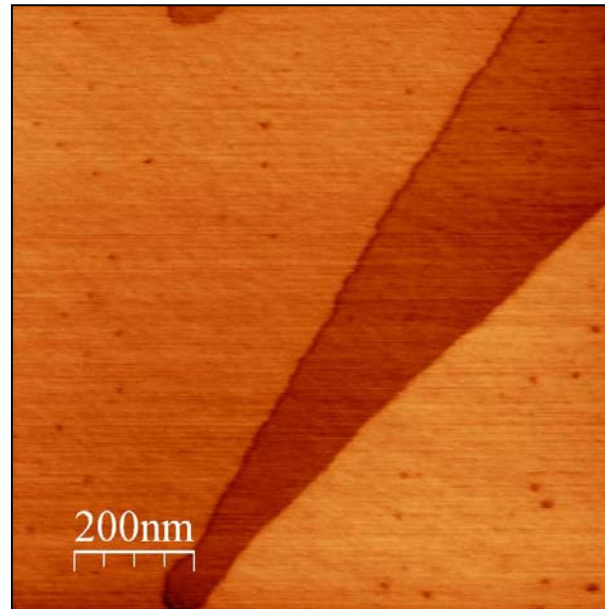
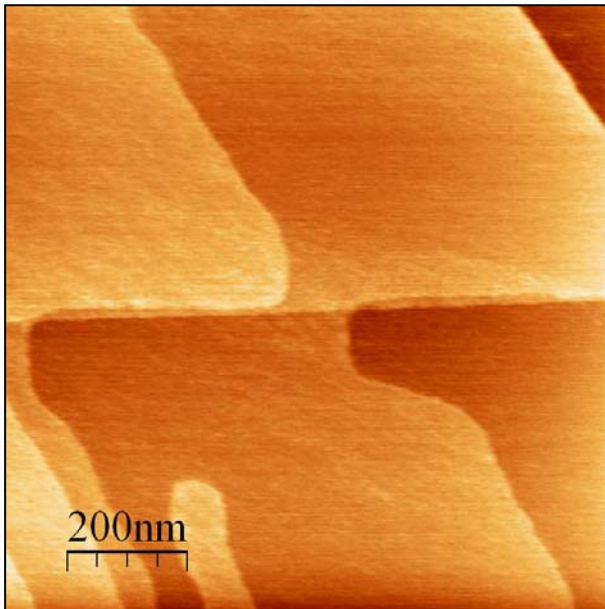
$E_{\text{kin}} = 1.0 \text{ keV}$

Xe^{34+} ($E_{\text{pot}} = 23 \text{ keV}$)

$E_{\text{kin}} = 40 \text{ keV}$

Xe^{34+} ($E_{\text{pot}} = 23 \text{ keV}$)

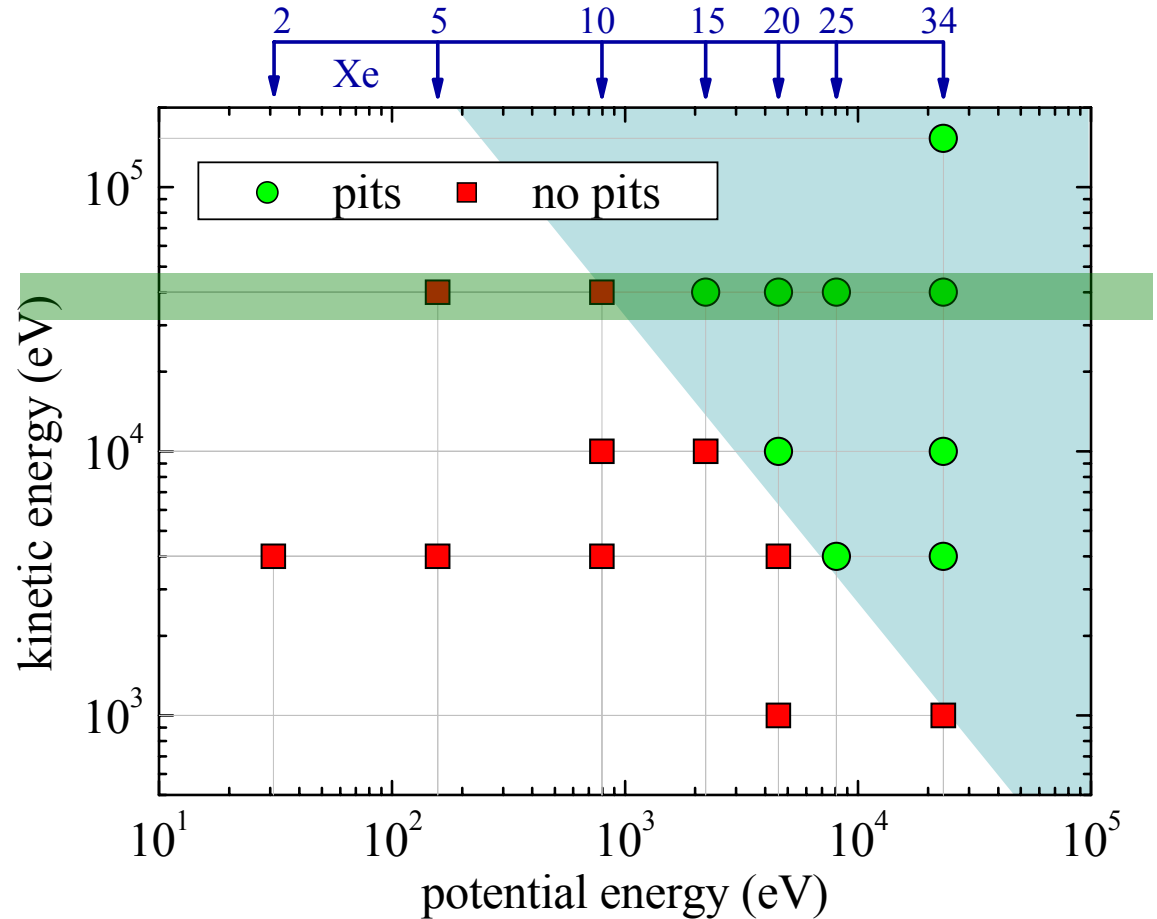
$E_{\text{kin}} = 153 \text{ keV}$



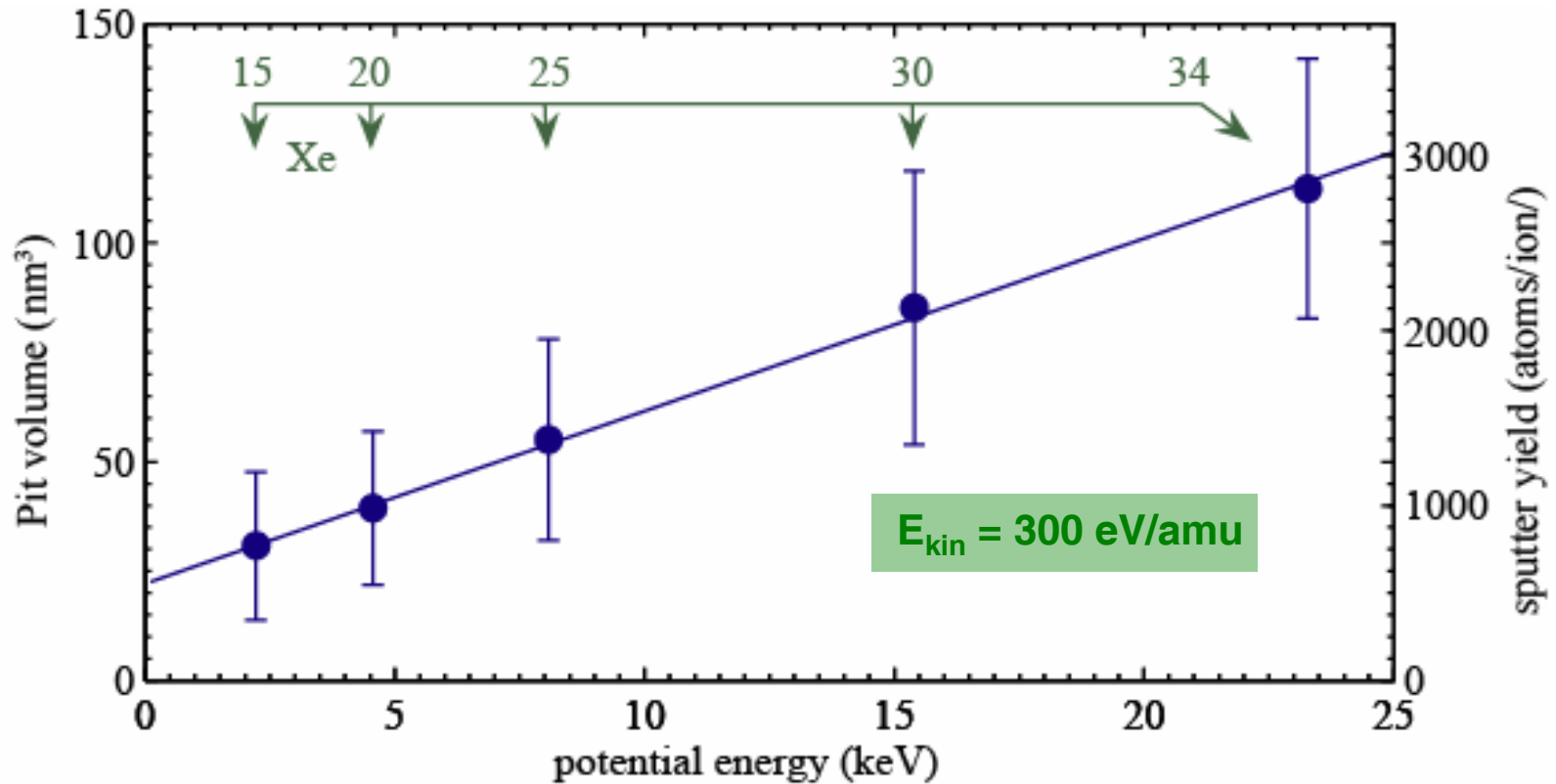
fluence $< 1 \cdot 10^{10} \text{ cm}^{-2}$

→ single ion impact

- Formation of pits depends strongly on **potential and kinetic energy**
- A threshold for the formation of pits exists in potential and kinetic energy
- Formation of pits is a synergistic effect!



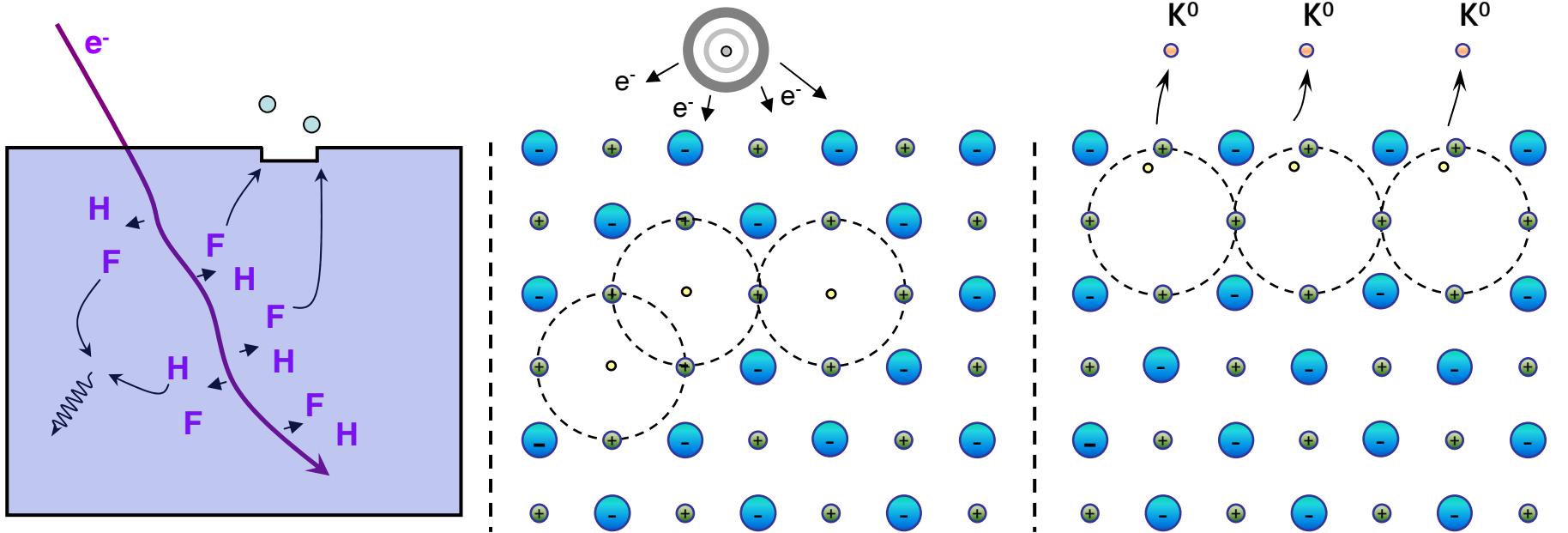
S. Facsko et al., J. Phys. Cond Matt. 21 (2009)



■ Pit volume and corresponding sputter yield show a linear dependence on the ions potential energy.

■ Pit depth is constant at one ML independent on E_{pot}

The X center

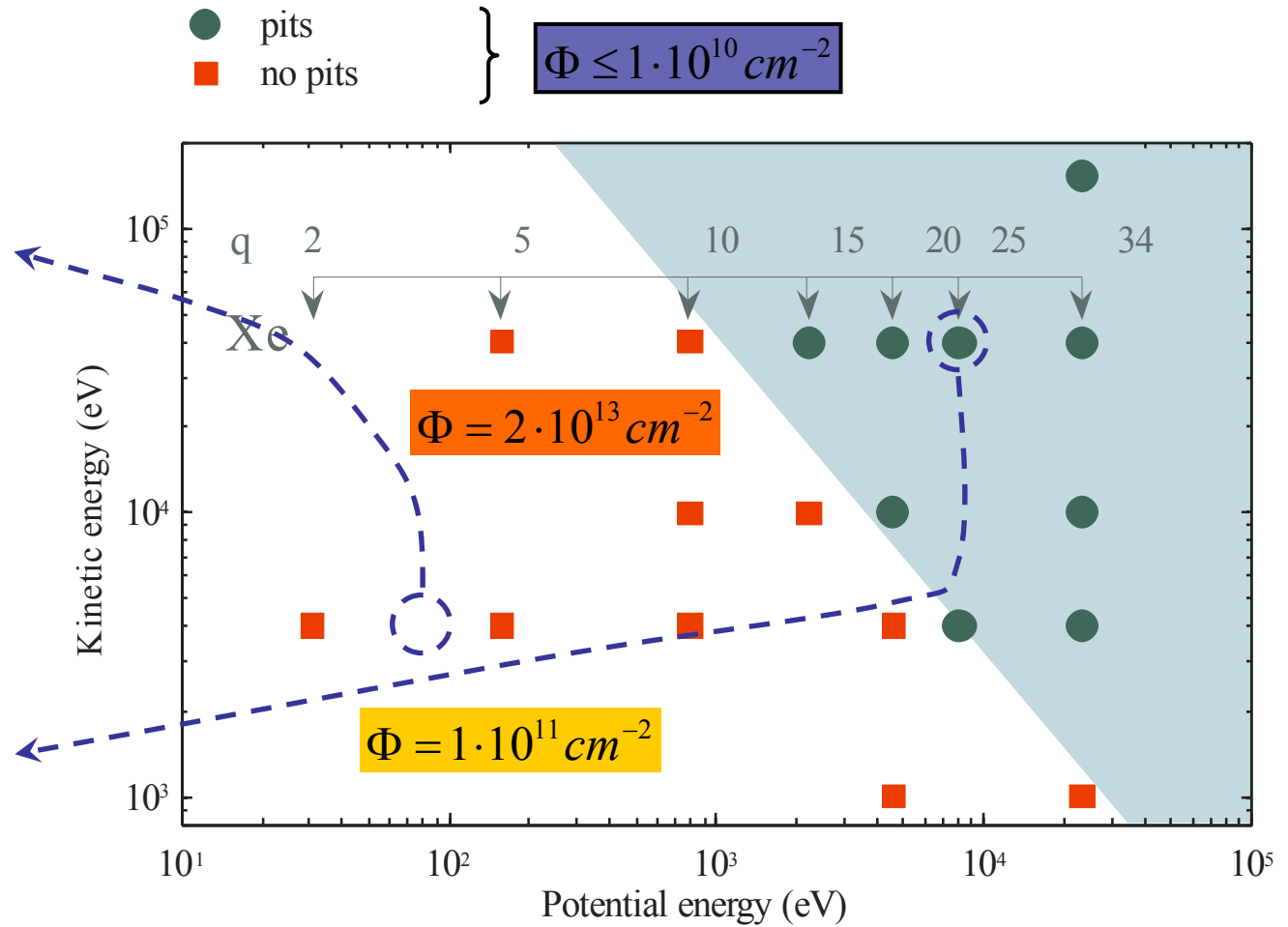
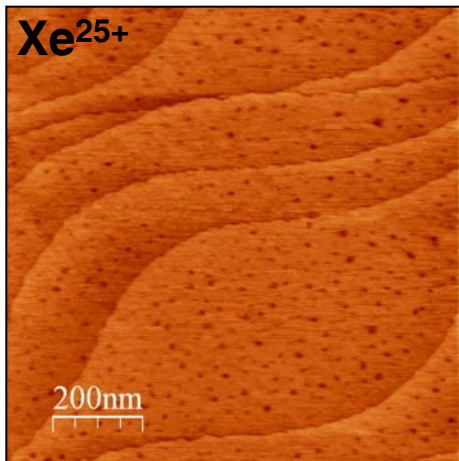
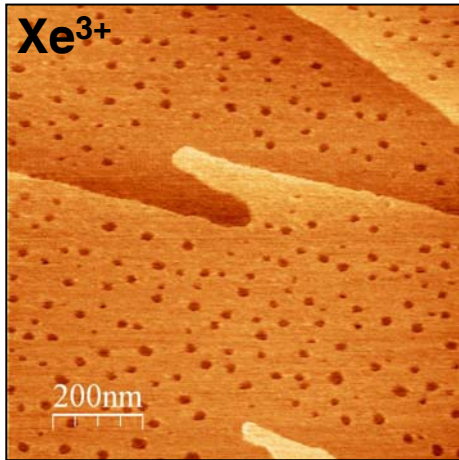


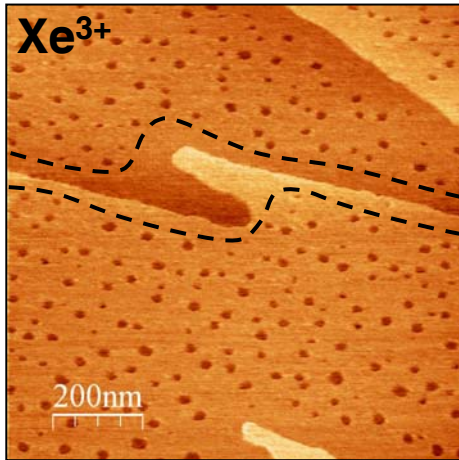
■ H and F center creation along the full electron trajectory

■ Cluster of 3 F-centers (X-center) created by multi-electron impact in HCl neutralization

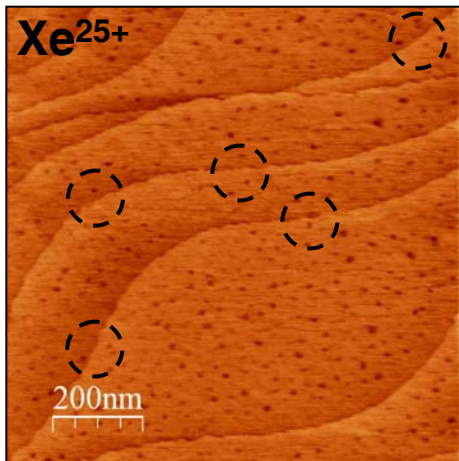
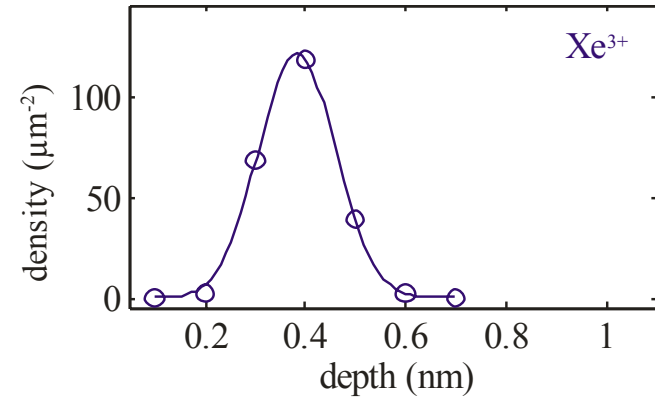
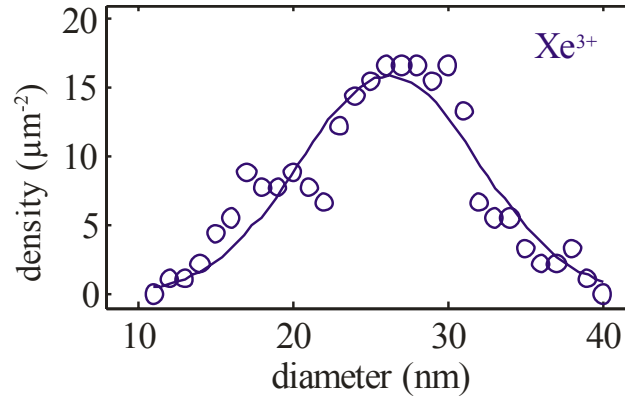
■ Cluster of 3 F-centers recombining with the surface by desorption of 3 K^0 atoms

R. Heller, R. Wilhelm, S. Facsko, PRL **101**, 096102 (2008)

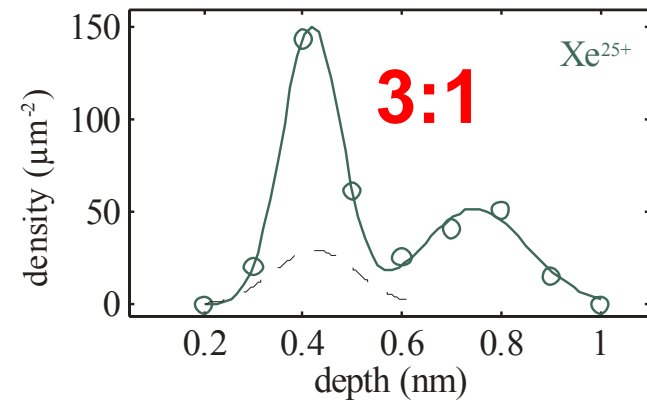
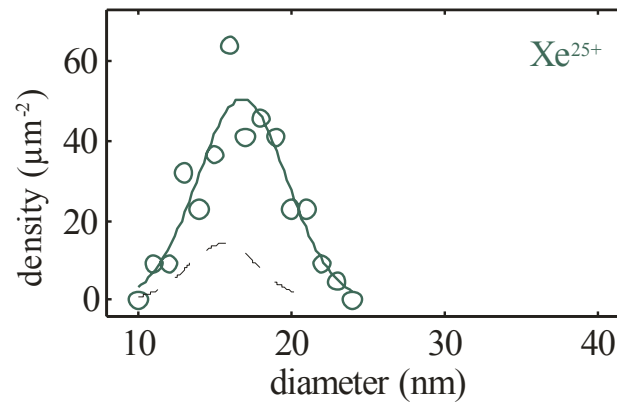




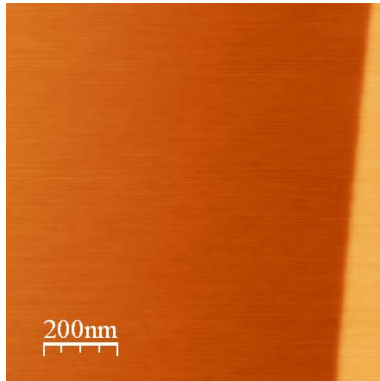
$\Phi = 2 \cdot 10^{13} \text{ cm}^{-2}$



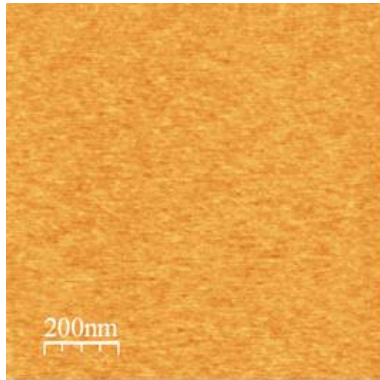
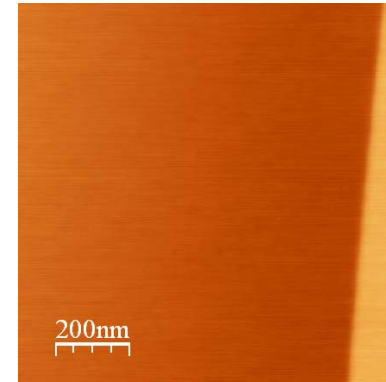
$\Phi = 1 \cdot 10^{11} \text{ cm}^{-2}$



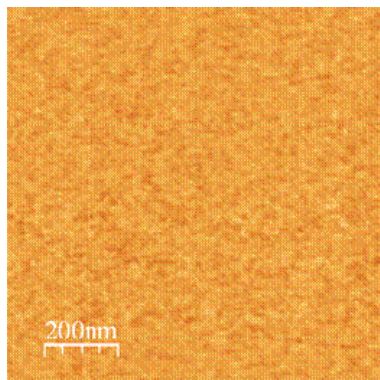
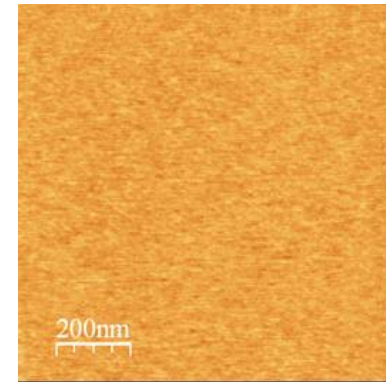
Etch pits on BaF_2 induced by highly charged ions



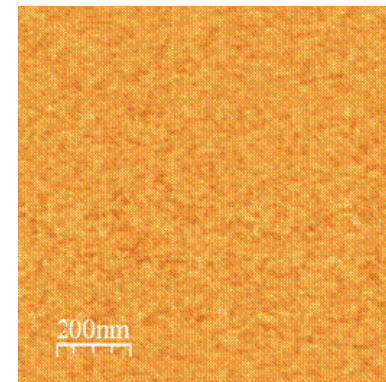
Xe²⁴⁺, E_{kin} = 4.5keV·q



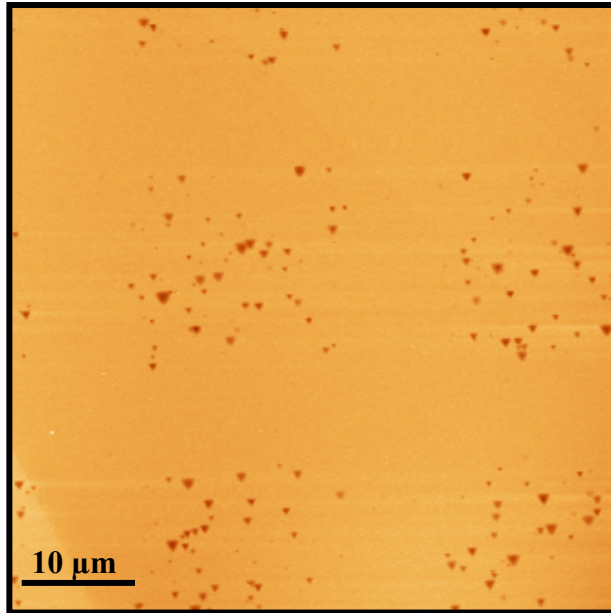
Xe³³⁺, E_{kin} = 4.5keV·q



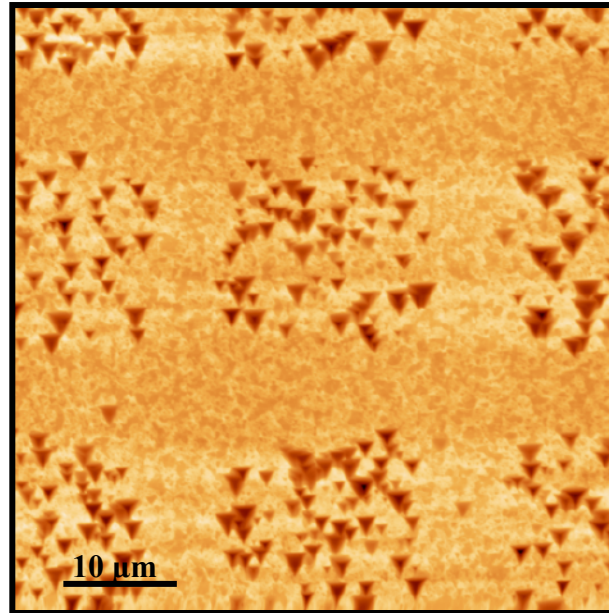
Xe³⁶⁺, E_{kin} = 4.5keV·q



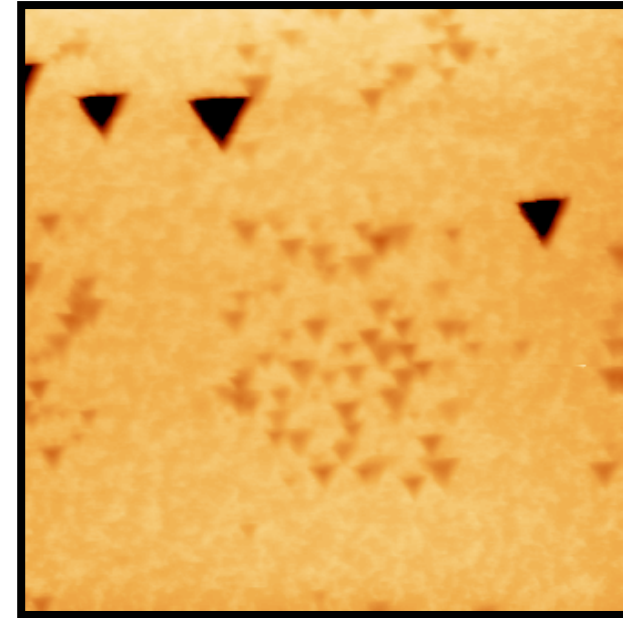
- Same samples after etching for 5s with 1 vol.% solution of HNO₃



Xe²⁴⁺, E_{kin} = 4.5keV·q

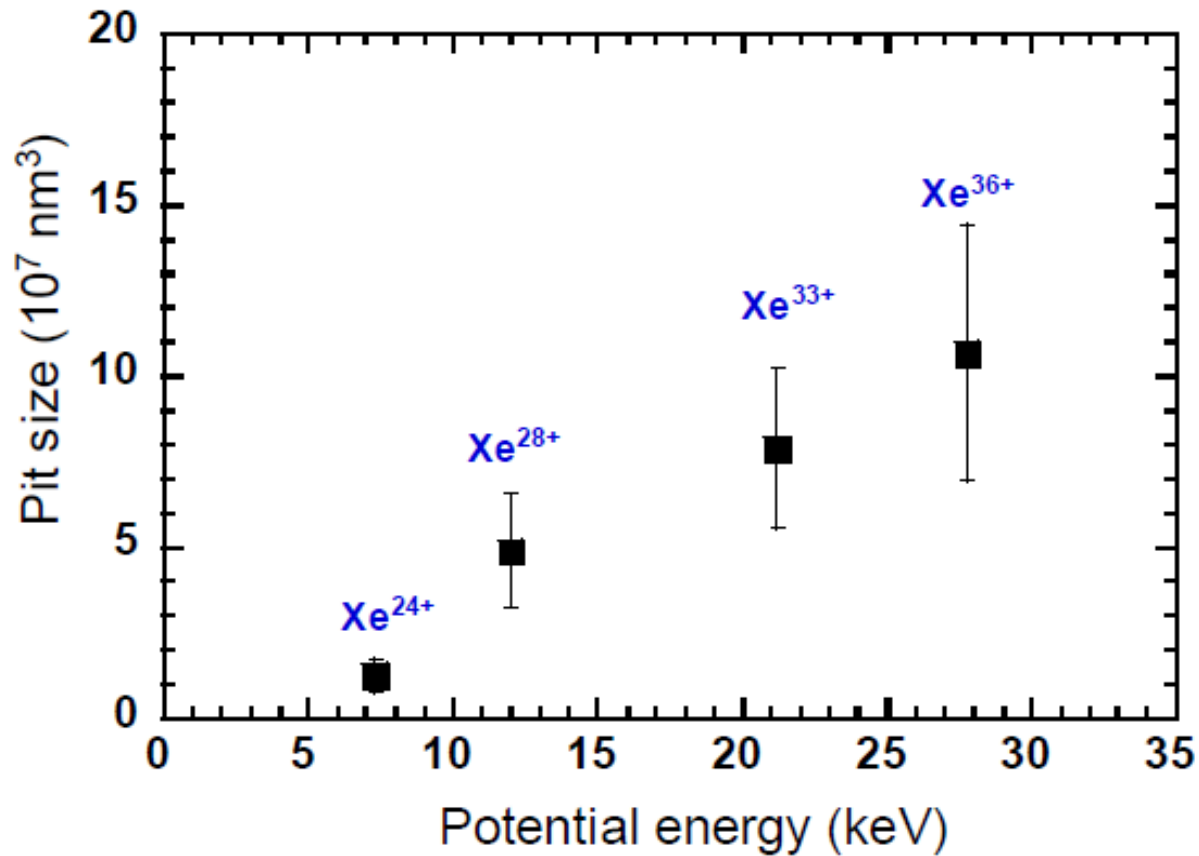


Xe³³⁺, E_{kin} = 4.5keV·q



Xe³⁶⁺, E_{kin} = 4.5keV·q

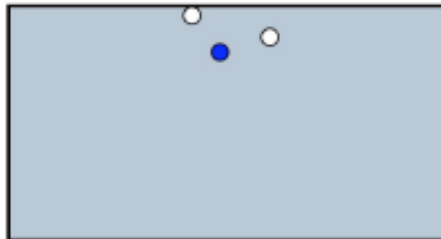
Potential energy create defects in the crystal!



Planned experiments at HITRAP: Xe⁵⁴⁺ and U⁹²⁺ at 4 MeV/u and 500 keV/u

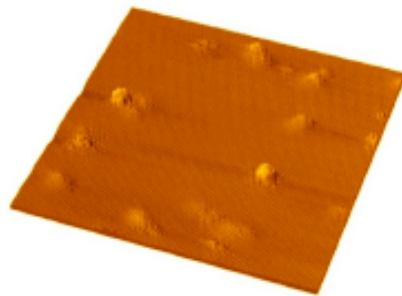
A. S. El-Said, R. Heller, S. Facsko and F. Aumayr, PRB (2010)

low q

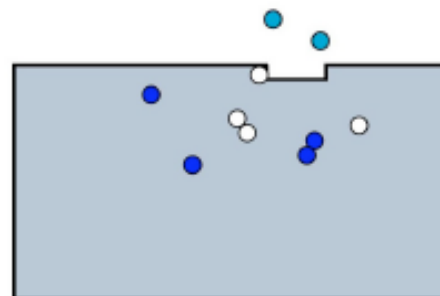


single defects

**electronic defects
modified friction**

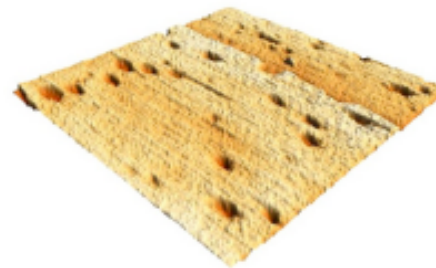


medium q

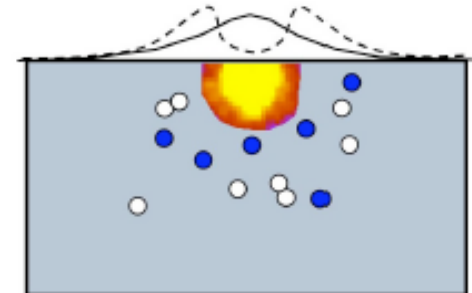


defect clusters

**potential sputtering
pits, craters**

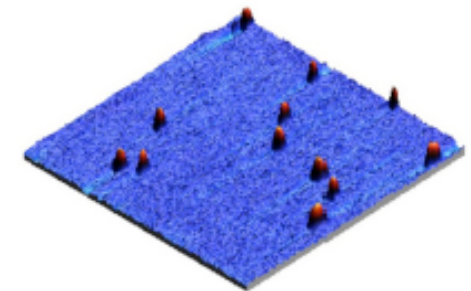


high q

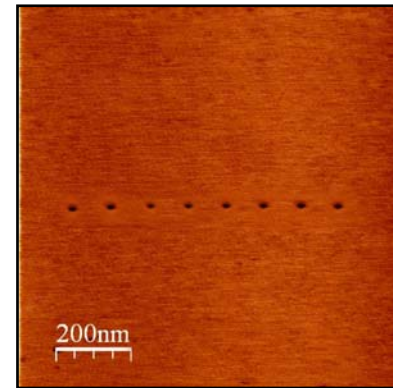
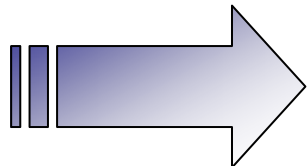
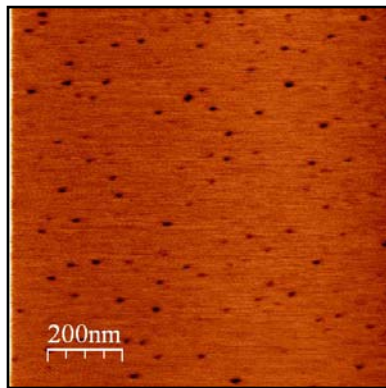
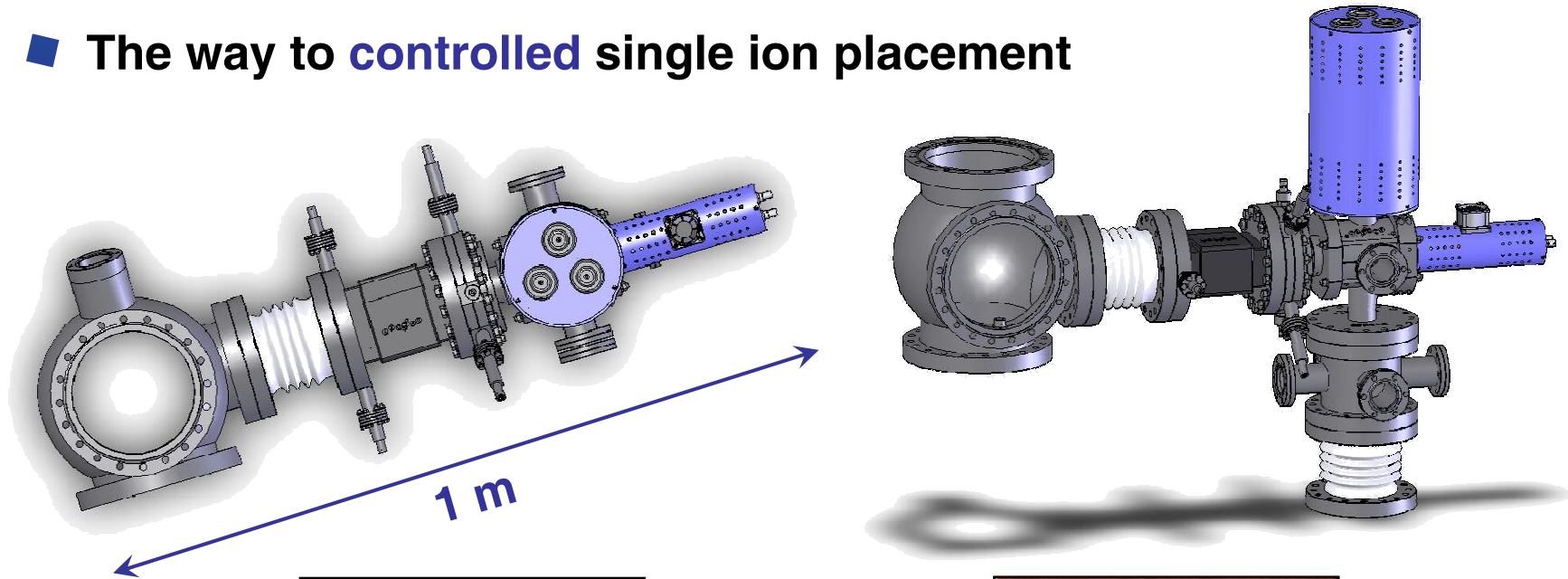


phase transitions

**surface melting
hillocks, calderas**



■ The way to **controlled** single ion placement



Goal!

- HCl_s can initiate the formation of **individual nano structures** of **different types** on various insulators
- Structure-formation depends on both the **potential** and (indirectly) **on** the kinetic energy of the ions
- Pit formation on KBr can be ascribed to a **special kind** of defect mediated desorption: X center formation
- The modified **inelastic thermal spike** model can successfully explain the hillock formation on CaF₂
- Further investigation on structure formation and **electron emission** are in progress

Thank you for your attention!